

Symposium (Oral) | Symposium | Pioneering of Frontier technology for metal oxide novel device I -from thin film fabrication to device creation -

[10p-W241-1~8]Pioneering of Frontier technology for metal oxide novel device I -from thin film fabrication to device creation -

Kosaku Shimizu(Nihon Univ.), Mutsumi Kimura(Ryukoku Univ.)

Sun. Mar 10, 2019 1:30 PM - 5:15 PM W241 (W241)

△ : Presentation by Applicant for JSAP Young Scientists Presentation Award

▲ : English Presentation

▼ : Both of Above

No Mark : None of Above

3:30 PM - 4:00 PM

[10p-W241-5]Electronic structures, materials design, and growth conditions for oxide semiconductors and devices

○Toshio Kamiya^{1,2}, Hideo Hosono^{1,2} (1.MSL, Tokyo Tech, 2.MCES, Tokyo Tech)

Keywords:oxide semiconductor